

# IHP 0.25 and 0.13 μm PROTOTYPING AND VOLUME PRODUCTION

EUROPRACTICE provides access to IHP SiGe:C BiCMOS Technologies for Multi-Project-Wafer Prototyping and Small Volume Production.

## **Technology Highlights**

# Why EUROPRACTICE?

- Affordable and easy access to Prototyping and Small Volume Production services for academia and industry.
- MPW (Multi-Project-Wafer) runs for various technologies, including ASICs, Photonics, MEMS and more.
- Advanced packaging, system integration solutions and test services.

## Why IHP?

- The world fastest Si-based RFtechnologies and monolithic photonic BiCMOS solutions, providing integrated HBTs with cutoff frequencies of up to 500 GHz.
- Very small minimum block size (0.8 mm<sup>2</sup>) for MPW for all technologies.
- Easy to install PDK and customerfriendly layout rejection test.
- Building a bridge between research and industry.

### 0.13 µm SG13 & 0.25 µm SG25

IHP offers research partners and customers worldwide access to its powerful SiGe:C BiCMOS technologies and special integrated RF modules. IHP technologies are based on  $0.13\mu m$  /  $0.25\mu m$  CMOS process. Several generations of high-speed SiGe Heterojunction Bipolar Transistors (HBT), passive components, such as poly resistors and MIM capacitors, have been developed and integrated in  $0.25\mu m$  and  $0.13\mu m$  BiCMOS technologies which are available for chip fabrication via IHP's MPW and prototyping service.

The 0.13µm BiCMOS process SG13G2 represents the fastest currently available SiGe HBT technology featuring peak  $f_T/f_{max}$  values of 300 GHz/500 GHz. These developments were based on a series of pioneering contributions to the development of SiGe HBTs including the introduction of carbon doping for stabilizing steep base doping profiles and new device constructions with reduced parasitic resistances and capacitance.

These IHP technologies are especially suited for applications in the higher GHz bands, e.g., for telecommunications & broadband (Gigabit WLAN, wireless sensor networks, wireless security solutions, fiber optic circuits), radar, medical imaging applications, aerospace, short-range detection for automotive, image sensor and motion recognition.

**SGI3S** is a high-performance 0.13 $\mu$ m BiCMOS with npn-HBTs up to  $f_T/f_{max} = 250/300$  GHz, including CMOS logic.

**SGI3G2** is a very high-performance 0.13 $\mu$ m BiCMOS technology with the same device portfolio as SGI3S but with a much higher bipolar performance with  $f_T/f_{max}$  = 300/500 GHz.

**SGI3G2Cu** and **SGI3SCu** is a FEOL process SGI3S and SGI3G2 together with Cu BEOL option from X-FAB containing Copper and Aluminum layer.

**SGI3G3Cu** is the highest performance HBT with up to 470GHz transit frequencies and up to 650 GHz maximum oscillation frequencies. The process offers an 8-layer Cu-BEOL from X-FAB.

**SG25H3** is a 0.25µm technology with a set of npn-HBTs ranging from a higher RF performance  $(f_T/f_{max} = 110/180 \text{ GHz})$  to higher breakdown voltages up to 7 V.

**SGB25V** is a cost-effective technology with a set of npn-HBTs up to a breakdown voltage of 7V.

**TSV (Through Silicon Vias)** is an additional option in SG13S and SG13G2 technology, which offers RF grounding by vias through silicon to improve RF performance.

**LBE (The Localized Backside)** is offered to remove silicon locally to improve passive performance (available in all technologies).

**MEMRES** is a fully CMOS integrated memristive module based on resistive TiN / HfO2-x / TiN switching devices in the SGI3S technology.

## Electronic Photonic IC Technology - SG25H5EPIC

SG25H5\_EPIC is the monolithic integration of photonic devices, such as detectors and modulators, in the frontend of a Si-based integrated circuit technology that allows shortest possible interconnects between photonics and electronics, from which high-speed performance of Electronic-Photonic Integrated Circuits (EPIC) greatly benefits.

The PDK features include Luceda IPKISS support for photonic designs (including simulation using Caphe ) and Cadence support for electronic – photonic circuit design (DRC, LVS, QRC).

This technology is especially suited for Optical Transceivers for 100G/200G/400 GHz applications.

## **Technology Details**

#### 0.13µm SG13S/C

Bipolar: High-speed HBT Ft/Fmax/BVceo: 250 GHz/330 GHz/1.7V High-voltage HBT Ft/Fmax/BVceo: 40 GHz/120 GHz/3.7V CMOS logic:Vdd = 1.2V CMOS l/O: Vdd = 3.3 V, 1.2 V Core voltage Passives:Poly-Si resistors, MOS varactors, Inductors MIM Cap. 1,5 fF/ µm<sup>2</sup> Interconnects: Backend offers 7 layers Al incl. 2 & 3 µm layers

#### 0.13 µm SG13G2

Bipolar: High-speed HBT Ft/Fmax/BVceo: 300 GHz/500 GHz/1.6 V High-voltage HBT Ft/Fmax/BVceo: 120 GHz/330 GHz/2.5 V CMOS logic:Vdd = 1.2 V CMOS l/O:Vdd = 3.3 V, 1.2 V Core voltage Passives: Poly-Si resistors, MOS varactors, Inductors MIM Cap. 1,5 fF/ µm<sup>2</sup> Interconnects: Backend offers 7 layers Al incl. 2 & 3 µm layers

#### 0.13µm SG13S Cu/G2Cu/G3Cu

IHP SG13S/G2 FEOL device performance and XFab Cu BEOL
MIM Cap. 2, I fF/ µm<sup>2</sup>
Interconnects:
Backend offers 8 layers:
6 layers Cu: 4 thin, 2 thick plus
2 Al top metal layers
6-layer Cu and 2-layer Al option from X-FAB

#### 0.25µm SGB25V

npn-HBTs up to Ft/Fmax = 95/75 GHz Vbce0 up to 7V Passives:Poly-Si resistors, MOS varactors, Inductors MIM Cap. I ff/ µm<sup>2</sup> Interconnects: Backend offers 3 thin metal layers, a MIM layer and 2 thick metal layers (TMI:2 µmTM2:3 µm)

#### 0.25µm SG25H3

npn-HBTs up to Ft/Fmax = 110/180 GHz Vbce0 up to 7V Passives: Poly-Si resistors, MOS varactors, Inductors MIM Cap. 1 fF/ μm<sup>2</sup> Interconnects: Backend offers 3 thin metal layers, a MIM layer and 2 thick metal layers (TM1:2 μmTM2:3 μm)

#### 0.25µm SG25H5\_EPIC

npn-HBTs up to Ft/Fmax = 220/290 GHz Germanium-PhotoDiode, WaveGuide, Full photonic device set for C/O-band Passives:Poly-Si resistors, MOS varactors, Inductors MIM Cap. IfF/ µm<sup>2</sup> Interconnects: Backend offers 3 thin metal layers a MIM layer and 2 thick metal layers (TMI: 2 µm TM2: 3 µm)

Would you like to discover more?

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